

**SECTION II—CLAIMS**

1. (Previously Presented) A method, comprising:
  - forming a cladding material over a substrate;
  - lithographically patterning and etching the cladding material to obtain core regions and a spacing between the core regions that is made of the cladding material;
  - filling the core regions with a core material;
  - using a chemical-mechanical process to remove excess core material formed over the core regions and over the cladding material; and
  - forming another cladding material over the core regions and over the spacing.
2. (Original) The method of claim 1 wherein etching the cladding material comprises using an anisotropic etching technique.
3. (Original) The method of claim 1 wherein filling the core regions comprises using a deposition technique.
4. (Original) The method of claim 1 wherein filling the core regions comprises using a re-flow process.
- 5.-6. (Canceled)
7. (Original) The method of claim 1 wherein lithographically patterning the cladding material includes using a mask.
- 8.-15. (Canceled)
16. (Currently Amended) A device, comprising:
  - a spacing made of a first cladding material and formed by an etch process to remove portions of the first cladding material from core regions adjacent to the spacing;
  - a core material filled into the core regions subsequent to removal of portions of the first cladding material from the core regions, wherein excess core material over the core regions and the spacing is removed through a chemical-mechanical process; and

a layer made of a second cladding material and formed over the core material and over the first cladding material, including over the spacing.

17. (Original) The device of claim 16 wherein the first and second cladding materials comprise a similar material having a lower refraction index than the core material.
18. (Original) The device of claim 16 wherein upper surfaces of the core material, of the spacing, and of the first material are substantially flush.
19. (Original) The device of claim 16 wherein the core regions and spacing are patterned using a lithography technique.
- 20.-21. (Canceled)
22. (Previously Presented) The device of claim 16 wherein the core regions are filled with the core material using a deposition or re-flow technique.